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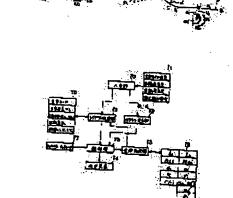
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(54) CHARACTER PROCESSING SYSTEM

(57) Abstract:

PURPOSE: To facilitate altering a layout and to improve working efficiency by considering the character layout to be one group of characters supervised by a guide line and calculating the relative position relationship between characters.

CONSTITUTION: When the guide line (b) is generated to alter the guide line 9a) in accordance with the correction of the layout, a conversion processing part 78 obtains a magnification (e) from the length of the guide line (b) with respect to the guide line (a), and further obtains the length ld of the guide line (b), a distance P'0c'i from a start point P'0 to an intersection c'i, and the relative position relationship between a character size (XSi, SYi), the length d'i of a perpendicular Hi at each intersection c'i, the inclination ϕ'i of the perpendicular Hi, a character position m'i. rotational angle ?'i, etc., according to commands altering a character size, the length of a perpen dicular and a rotational angle instructed by an input part 70 separately, and stores said relationship in a memory part 79. When the relative position



relationship of the character with respect to the guide line (b) is obtained in such a way, a layout processing part 75 executes the layout processing according to the relative position relationship obtained in the alteration processing part 78, and outputs the layout result to an output device 74.

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